



Mass Spectrometry Solutions

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Cirrus™ 3-XD

THE ULTIMATE PERFORMANCE FOR ATMOSPHERIC PRESSURE GAS MONITORING

Designed for researchers and engineers who need to work beyond the limits of conventional quadrupole MS technology - to more easily detect and monitor trace gases - the Cirrus™ 3-XD system delivers a unique analytical advantage for eXtreme Detection capability.

The proven Cirrus Quadrupole MS platform now utilizes patented, V-lens™ ion optics with a double-focussing and deflection capability - to produce a consistently low baseline for any gas species - enabling trace level detection with greater clarity and confidence than ever before.

With its versatile, compact design and powerful, automatable software control, the Cirrus 3-XD system provides a new level in performance, robustness and ease-of-use for the most challenging trace gas analyses.

Cirrus systems are ideal for the on-line monitoring and analysis of gases and gas mixtures including trace contaminants in process gases; solvent vapors; hydrocarbons; atmospheric and inorganic gas species (including corrosives); freons and noble gases.

Cirrus systems are easy to install and operate, featuring automatic start-up and shut-down routines as well as built-in vacuum and heater interlocking for system protection. Cirrus 3-XD is manufactured from quality field proven materials which maximize reliability and uptime. Particular consideration has been paid to ease of service and maintenance.

Features & Benefits

Powerful, Fast, Stable and Robust

- V-lens technology - for a gas-independent low baseline, and robust detection to low ppb levels
- Wide dynamic range, enabling detection across a wide range of concentrations from trace levels (low ppb) to high abundance (percentage levels)
- Supreme temperature stability with unique oven design offering stable and reliable performance
- Fast response – 250 data points per second, and silica capillary inlet heated to 150°C, for sampling different gas conditions with multiple inlet options:
 - Stainless steel capillaries
 - Low flow capillaries
- Automated variable pressure inlet, enabling accurate profiling of pure gases and gas mixtures

Versatile and Easy-to-Use

- Convenient benchtop and rack-mounted configurations
- Versatile recipe-driven Process Eye™ Professional software for automated operation and calibration
- Direct Ethernet interface - fully network compatible
- Compact, modular design for ease of serviceability and maintenance



Applications

- Monitoring trace contaminants to low ppb, in process gases of all types
- Gas purity and manufacturing QC
- Catalyst studies
- Fuel cell monitoring and development
- Environmental monitoring
- Thermal analysis - TGA, DTA
- Fermentation process monitoring
- Heat treatment/furnace monitoring
- Membrane studies
- Glove box gas monitoring
- Lamp manufacture
- Freon detection and identification

Introduction

Cirrus systems are based on Quadrupole mass spectrometry, widely acknowledged as a preferred technological platform for many atmospheric pressure gas analysis applications. The Cirrus 3-XD system, with its innovative V-lens ion optics and its compact mechanical design, provides a new level of performance and robustness in space efficient and flexible configurations that are ideal for a wide range of analytical applications and environments. Cirrus 3-XD is precision engineered to provide supreme speed and stability in response, with the ability to accurately detect and quantify gases and gas mixtures with a single analyzer. Gas composition can be monitored over a wide dynamic range, from percentage down to low ppb levels.

V-lens™ Technology

V-lens ion-optics technology uses a unique, patented double-focussing and deflection mechanism to significantly reduce background and enhance sensitivity. The result is an atmospheric pressure gas analyzer with low limits of detection (typically in the mid to low ppb range) without compromise to any other aspect of instrument performance - even when working with the most challenging gases that can produce large amounts of chemical background noise via metastable decay. This novel technological design provides significant improvements in quality and clarity in the data obtained, for any application where detecting the lowest levels of contamination with confidence is important.

Quadrupole Analyzer

At the heart of every Cirrus 3-XD system is a precision-built quadrupole analyzer incorporating a closed ion source, a triple mass filter and a dual (Faraday and Secondary Electron Multiplier) detector system. This analyzer configuration is selected to optimize sensitivity and long term stability performance.

Heating and Vacuum System

The Cirrus 3-XD offers very stable performance, by housing the entire vacuum chamber (with quadrupole analyzer) and inlet interface assembly inside a precision engineered convection oven design. This offers high temperature uniformity and eliminates potential cold spots, which could otherwise cause undesirable sample condensation and variance in analysis. The oven design features a convection heating mechanism and optimized insulation construction within a stainless steel housing, which provides low heat sink characteristics. The quadrupole analyzer itself is contained within a stainless steel vacuum chamber which is pumped by an oil free high compression turbomolecular/diaphragm pump combination. The vacuum system is backed by a 4-stage diaphragm pump, which is now contained within the instrument itself. Alternatively, the entire Cirrus 3-XD vacuum chamber can be baked to reduce residual gas background species and to minimize any memory effects.

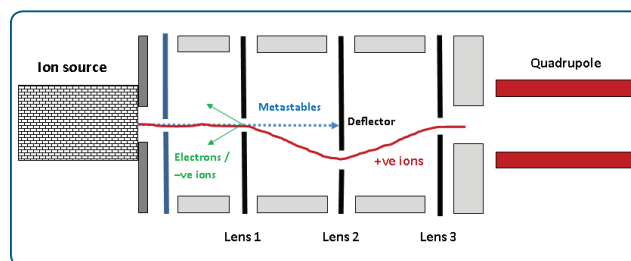
Gas Inlet

An essential feature of any gas analyzer is that it should not contaminate or alter the gas sample in any way. The Cirrus 3-XD inlet assembly consists of an inert silica lined capillary, which can be heated to a stable temperature.

The low volume and surface area of the assembly serves to maximize response speed while minimizing memory effects. Cirrus 3-XD systems can also be configured with inlets for multi-stream sampling, stainless steel capillaries for resistance to fluorine based compounds and a Baratron® (capacitance manometer) pressure controller inlet to allow sampling from supplies which vary from the nominal 1 bar inlet requirement. The Cirrus 3-XD vacuum system utilizes a high compression turbomolecular pump so light gases such as hydrogen and helium can be sampled with no additional expensive pumping requirements.

Maintenance and Access

The Cirrus 3-XD internal oven has a removable cover allowing easy access to the inlet interface, vacuum chamber and analyzer ion source. This is particularly helpful for routine maintenance like filament and capillary replacement. A cold cathode gauge is incorporated for independent vacuum pressure measurement and to provide an interlock signal for protection of the mass spectrometer. A temperature sensor also ensures that the electron multiplier detector cannot be switched on at high temperatures. The Cirrus 3-XD is designed with a lubricant free pumping system and no elastomer seals are used in the sample inlet system or in the high vacuum region of the system.



Novel V-lens™ Ion Optics Technology



Process Eye™ Professional Software

Cirrus 3-XD is operated using proven Process Eye Professional software, a recipe-driven platform that communicates with the system over a TCP/IP network. Process Eye Professional is designed for use with the latest Microsoft® operating systems including 32 bit or 64 bit Windows® XP, Vista, Server 2008 and Windows 7.

The features and benefits are as follows:

- Data presented in units relevant to the application
- Allows for fully automated operation and calibration
- Provides a new multipoint calibration workflow for quantitative applications
- User-configurable alarms and warnings
- Can be configured to track data from other process sensors (temperature, pressure, flow, etc.)

Options

- Corrosive gas sample version
- Regulated ion source pressure version for samples of varying pressure



Cirrus 3-XD 6U rack-mounted configuration

Specifications

Dimensions & Weight

Benchtop system	594mm L x 291mm W x 470mm H, 35 Kg
Rack-mounted system	577mm L x 482mm W x 266mm (6U) H, 35 Kg

Electronics

1 to 100, 100HP, 200 or 300 amu options

Detection Limits

Gas and Mass Independent - the minimum detectable concentration 3 sigma baseline noise is <15 ppb (specified with Argon or Nitrogen)

Electron Energy & Emission Current

Operator variable

Maximum Operating Temperature

(Turbo pump & electronics) 35°C, 80% RH (non-condensing)

Oven Temperature

(Vacuum chamber & inlet interface) 180°C for bakeout, 80°C setting for operation at elevated temperatures

Capillary Inlet

2.0m long with ¼" Swagelok® end connection, heated to 150°C (optional heating to 300°C, with stainless steel only). Standard fused silica and optional stainless steel.

Gas Consumption

20 ml/min, lower uptake rate capillaries options are available

Sample Pressure

1 bar nominal

Pumping System

High compression turbo-molecular pump with internal 4-stage diaphragm backing pump standard, corrosive gas pumping with all internal pumps optional

Automated Inlet Pressure Controller

A Baratron capacitance manometer based automated inlet pressure controller is available as an option

Recommended PC Spec

Microsoft 32 bit or 64 bit Windows 7 or 8.1

Computer Interface

1 x LAN port required

I/O Capability (Cirrus 2-based)

4 analog inputs (-11 to +11 volt, 22 bit)
2 analog outputs (0-10 volt, 12 bit)
16 TTL digital I/O

Power

Universal mains input 100 – 240 VAC / 50 – 60 Hz
Power supply specified at 700W. Maximum consumption(during bakeout) typically 300W

RoHS Compliance

Exempt to RoHS Directive 2002/95/EC



Ordering Information

Rack-mount Instrument Product Ordering Codes:

Non-process

Cirrus 3-XD (100 amu, non-process): 470-12E-A30
 Cirrus 3-XD (200 amu, non-process): 470-22E-A30
 Cirrus 3-XD (300 amu, non-process): 470-32E-A30

Process*

Cirrus 3-XD (100 amu, process): 470P-12E-A30
 Cirrus 3-XD (200 amu, process): 470P-22E-A30
 Cirrus 3-XD (300 amu, process): 470P-32E-A30

Desktop Instrument Product Ordering Codes:

Non-process

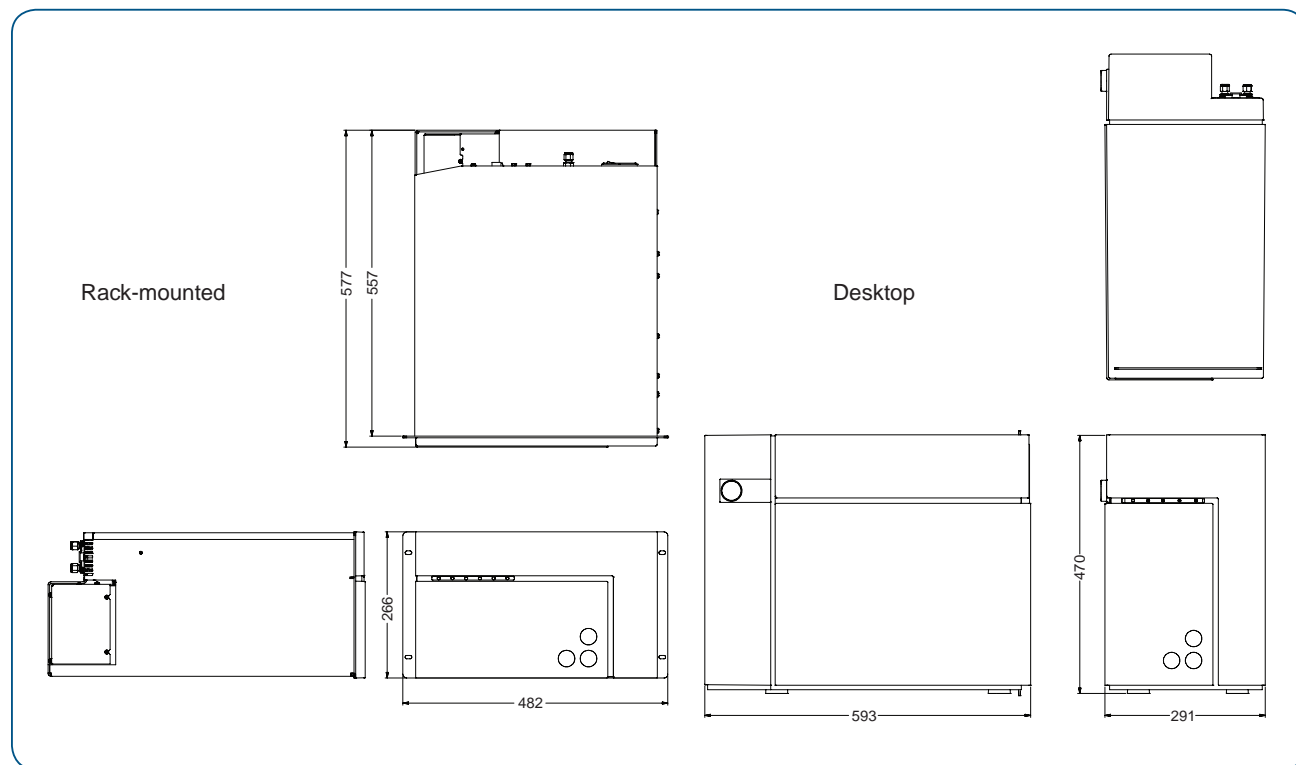
Cirrus 3-XD (100 amu, non-process): 471-12E-A30
 Cirrus 3-XD (200 amu, non-process): 471-22E-A30
 Cirrus 3-XD (300 amu, non-process): 471-32E-A30

Process*

Cirrus 3-XD (100 amu, process): 471P-12E-A30
 Cirrus 3-XD (200 amu, process): 471P-22E-A30
 Cirrus 3-XD (300 amu, process): 471P-32E-A30

* Process package includes on site applications start-up assistance

For other options such as filament type, corrosion resistance, inlet pressure control, lower inlet flow capillaries and capillary material and temperature, contact a local MKS sales office for applications assistance.



Dimensional Drawing —

Note: Unless otherwise specified, dimensions are nominal values in millimeters.



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